

L Number	Hits	Search Text	DB	Time stamp
1	2	20020042007.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 01:18
2	632775	356/\$.ccls. or (700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:58
5	612324	((metal or aluminum or alloy or chrom\$6 or metallic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:53
6	408605	photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:57
7	105923	(((metal or aluminum or alloy or chrom\$6 or metallic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) and (photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:14
8	39210	(356/\$.ccls. or (700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((metal or aluminum or alloy or chrom\$6 or metallic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) and (photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:14
10	39	((((metal or aluminum or alloy or chrom\$6 or metallic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) and (photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4)))) and 700/121.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:46
11	2	6185473.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:46
12	92692	((metal or aluminum or alloy or chrom\$6 or metallic or nickel or polysilicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:57
13	117170	(photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:57

14	27222	((metal or aluminum or alloy or chrom\$6 or metallic or nickel or polysilicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))) and ((photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 02:58
15	16607	(356/\$.ccls. or (700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((metal or aluminum or alloy or chrom\$6 or metallic or nickel or polysilicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))) and ((photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:10
16	712	702/81-84.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:05
18	3693	700/28,32,95,97,102,103,104,108-110,121.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:01
19	3594		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:02
21	4251		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:05
22	21		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:05

23	3307	((356/.ccls. or (700/.ccls. or 702/.ccls. or 438/.ccls. or 716/.ccls. or 430/.ccls. or 216/.ccls. or 257/.ccls.) or 382/144.ccls.) and (((metal or aluminum or alloy or chrom\$6 or metallic or nickel or moly silicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))) and ((photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3)))))) and ((trim\$4 or second) near2 (mask\$3 or photo-mask\$3 or photomask\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:12
24	1495	((356/.ccls. or (700/.ccls. or 702/.ccls. or 438/.ccls. or 716/.ccls. or 430/.ccls. or 216/.ccls. or 257/.ccls.) or 382/144.ccls.) and (((metal or aluminum or alloy or chrom\$6 or metallic or nickel or moly silicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))) and ((photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3)))))) and ((trim\$4 or second) near2 (mask\$3 or photo-mask\$3 or photomask\$3)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:11
25	30	((356/.ccls. or (700/.ccls. or 702/.ccls. or 438/.ccls. or 716/.ccls. or 430/.ccls. or 216/.ccls. or 257/.ccls.) or 382/144.ccls.) and (((metal or aluminum or alloy or chrom\$6 or metallic or nickel or moly silicide or moly-silicide or emulsion) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or psm or pellicle or coat\$4)) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))) and ((photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or photolithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3)))))) and ((trim\$4 or second) near2 (mask\$3 or photo-mask\$3 or photomask\$3)) with (threshold or target or limit).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:30
26	10	((mask\$3 or photo-mask\$3 or photomask\$3) near2 (menu)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:53
27	15	((mask\$3 or photo-mask\$3 or photomask\$3) near4 (menu)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:53

28		3 ((mask\$3 or photo-mask\$3 or photomask\$3) near4 (gui)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 03:54
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